

ABSTRACT

The present invention discloses a wafer cleaning apparatus and a cleaning method, which relate to the field of semiconductor equipment. The wafer cleaning apparatus comprises: a first tank, for containing cleaning liquid and a wafer; a second tank, for containing cleaning liquid; a spray mechanism, for spraying cleaning liquid onto the wafer; and a second circulation filtration pipeline, a liquid inlet of the second circulation filtration pipeline being connected to the first tank, the second tank being arranged on the second circulation filtration pipeline, and a liquid outlet of the second circulation filtration pipeline being connected to the spray mechanism, and the second circulation filtration pipeline discharging the cleaning liquid in the first tank into the second tank and transferring the cleaning liquid from the second tank to the spray mechanism. The cleaning liquid in the first tank can be discharged into the second tank through the second circulation filtration pipeline, and the wafer is spray-cleaned by means of the second circulation filtration pipeline and the spray mechanism, thereby improving the cleaning effect of the wafer.